

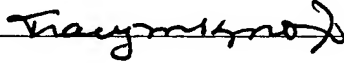
IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Ibrahim Abdulhalim, et al.
Title: Periodic Patterns And Technique To Control Misalignment Between Two Layers
Application No.: 10/699,153 Filing Date: October 30, 2003
Examiner: Unknown Group Art Unit: 1765
Docket No.: TNCR.196US2 Conf. No.: 1463

Certificate of Mailing Under 37 CFR 1.8

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Signature



Commissioner for Patents
P.O. Box 1450
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INFORMATION DISCLOSURE STATEMENT

Dear Sir:

Pursuant to 37 C.F.R. §§ 1.56, 1.97 and 1.98, Applicant(s) call(s) the documents listed on the enclosed Form PTO-1449 to the Examiner's attention in this patent application.

Copies of the documents listed on the accompanying Form PTO-1449 are enclosed.

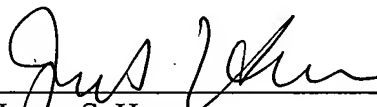
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Attorney Docket No.:
TNCR.196US2

Application No.:
10/699,153

This information disclosure statement is submitted under 37 C.F.R. § 1.97(b) and consequently no fee should be required. The Commissioner is authorized, however, to charge any fee that may be required, or to credit any overpayment, against Deposit Account No. 502664. This form is being submitted in duplicate.

Respectfully submitted,



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3/1/04

Date

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U.S. Department of Commerce, Patent and Trademark INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary)				Atty. Docket No. TNCR.196US2		Application No. 10/699,153	
				Applicant(s) Ibrahim Abdulhalim, et al.		Conf. No. 1463	
				Filing Date October 30, 2003		Group 1765	
U.S. Patent Documents							
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
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	2	4,167,337	Sep. 11, 1979	Jaerisch et al.			
	3	4,631,416	Dec. 23, 1986	Trutna, Jr.			
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							Translation	
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	81	"Interferometric Measurement System for Overlay Measurement in Lithographic Processes", IBM TDB, Feb. 1994.						
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	88	“Characterization and Monitoring of Variable NA and Variable Coherence Capable Photo Steppers Utilizing the Phase Shift Focus Monitor Reticule”, Journal: Proceedings of the SPIE, vol. 2439, p. 61-9. (Abstract)	
	88	“Modeling of Optical Scatterometry with Finite-Number-of-Periods Grating”, Journal: Proceedings of the SPIE, vol. 3743, p. 41-8. (Abstract)	
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	88	“A Mask-to-Wafer* Alignment and Gap Setting Method for E-Ray Lithography Using Gratings”, Journal: Journal of Vacuum Science & Technology B. vol. 9, no. 6. p. 3202-6. (Abstract)	
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	88	“Performance of New Overlay Measurement Mark”, Sung-Man Bae and Ki-Ho Baik, SPIE, vol. 2725 p. 424-435.	
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	94	“Super Sparse Overlay Sampling Plans: An Evaluation of Methods and Algorithms for Optimizing Overlay Quality Control and Metrology Tool Throughput”, Pellegrini et al., SPIE, vol. 3677, p. 72-82, March 1999.	
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	100	“Alignment Mark Optimization to Reduce Tool and Wafer-Induced Shift for XTRA-1000”, Ina et al., Japanese Journal of Applied Physics, vol. 38, no. 12B, p. 7065-70. (Abstract)	
	101	“Towards the Optimal Design of Binary Optical Elements with Different Phase Levels Using a Method of Phase Mismatch Correction”, Kodate et al., Trends in Optics and Photonics, vol. 41, p. 174-6. (Abstract)	
Examiner		Date Considered	
<p>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.</p>			